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(54) Title: PROCESSING CHAMBER

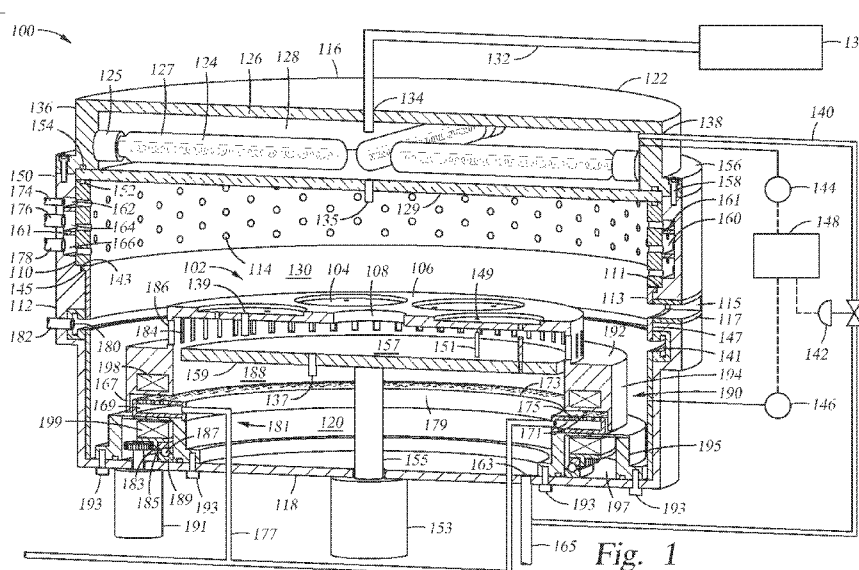


Fig. 1

(57) Abstract: Embodiments of the present disclosure provide a processing chamber with a top, a bottom, and a sidewall coupled to -
together to define an enclosure, a gas distributor around the sidewall, a substrate support disposed in the enclosure, the substrate sup-
port having a central opening and a plurality of substrate locations distributed around the central opening, a pumping port below the
substrate support, and an energy source coupled to the top or the bottom. The energy source may be a radiant source, a thermal
source, a UV source, or a plasma source. The substrate support may be rotated using a magnetic rotator and an air bearing. The gas
distributor may have a plurality of passages distributed around a circumference of the gas distributor.